

AMENDMENTS TO THE CLAIMS

1-2. (Cancelled)

3. (Currently amended) ~~The baffle plate assembly of claim 1,~~ A baffle plate assembly for surrounding a substrate holder in a plasma processing system comprising:

a centering ring configured to be coupled to said substrate holder, wherein at least a portion of said centering ring extends radially outside a periphery of said substrate holder; and
a removable baffle plate comprising one or more passageways, wherein said baffle plate is configured to be centered within said plasma processing system by removably coupling said baffle plate to said portion of said centering ring extending radially outside said periphery of said substrate holder, and

wherein said centering ring comprises a centering feature configured to center said baffle plate on said centering ring.

4. (Original) The baffle plate assembly of claim 3, wherein said centering feature comprises at least one of a centering pin, a centering receptacle, a centering edge, and radial face gear teeth.

5. (Original) The baffle plate assembly of claim 3, wherein said baffle plate comprises a mating feature configured to be coupled with said centering feature.

6. (Original) The baffle plate assembly of claim 5, wherein said mating feature comprises at least one of a centering pin, a centering receptacle, a centering edge, and radial face gear teeth.

7. (Currently amended) ~~The baffle plate assembly of claim 1;~~ A baffle plate assembly for surrounding a substrate holder in a plasma processing system comprising:

a centering ring configured to be coupled to said substrate holder, wherein at least a portion of said centering ring extends radially outside a periphery of said substrate holder; and

a removable baffle plate comprising one or more passageways, wherein said baffle plate is configured to be centered within said plasma processing system by removably coupling said baffle plate to said portion of said centering ring extending radially outside said periphery of said substrate holder, and

wherein said centering ring is made from aluminum.

8. (Cancelled)

9. (Currently amended) ~~The baffle plate assembly of claim 1;~~ A baffle plate assembly for surrounding a substrate holder in a plasma processing system comprising:

a centering ring configured to be coupled to said substrate holder, wherein at least a portion of said centering ring extends radially outside a periphery of said substrate holder; and

a removable baffle plate comprising one or more passageways, wherein said baffle plate is configured to be centered within said plasma processing system by removably coupling said baffle plate to said portion of said centering ring extending radially outside said periphery of said substrate holder, and

wherein a surface of said baffle plate comprises a protective barrier.

10. (Currently amended) ~~The baffle plate assembly of claim 1,~~ A baffle plate assembly for surrounding a substrate holder in a plasma processing system comprising:

a centering ring configured to be coupled to said substrate holder, wherein at least a portion of said centering ring extends radially outside a periphery of said substrate holder; and

a removable baffle plate comprising one or more passageways, wherein said baffle plate is configured to be centered within said plasma processing system by removably coupling said baffle plate to said portion of said centering ring extending radially outside said periphery of said substrate holder, and

wherein a portion of a surface of said baffle plate comprises a protective barrier.

11. (Original) The baffle plate assembly of claim 9 or 10, wherein said protective barrier comprises at least one of surface anodization, a coating formed using plasma electrolytic oxidation, and a spray coating.

12. (Original) The baffle plate assembly of claim 9 or 10, wherein said protective barrier comprises a layer of at least one of a III-column element and a Lanthanone element.

13. (Original) The baffle plate assembly of claim 9 or 10, wherein said protective barrier comprises at least one of Al_2O_3 , Yttria (Y_2O_3), Sc_2O_3 , Sc_2F_3 , YF_3 , La_2O_3 , CeO_2 , Eu_2O_3 , and DyO_3 .

14-16. (Cancelled)

17. (Previously Presented) A method of replacing a baffle plate disposed adjacent a centering ring with at least a portion of said centering ring extending radially outside a periphery of a substrate holder, said baffle plate surrounding said substrate holder in a plasma processing system, the method comprising:

removing said first baffle plate from said centering ring in said plasma processing system, and

installing a second baffle plate in said plasma processing system by coupling said second baffle plate to said centering ring, wherein said coupling facilitates autocentering of said second baffle plate in said plasma processing system.